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Supporting Information

Inherent Area-Selective Atomic Layer Deposition of ZnS

Chao Zhang*, Marko Vehkamäkia, Markku Leskelä, Mikko Ritala

Department of Chemistry, University of Helsinki, P.O. Box 55, 00014 Helsinki, Finland

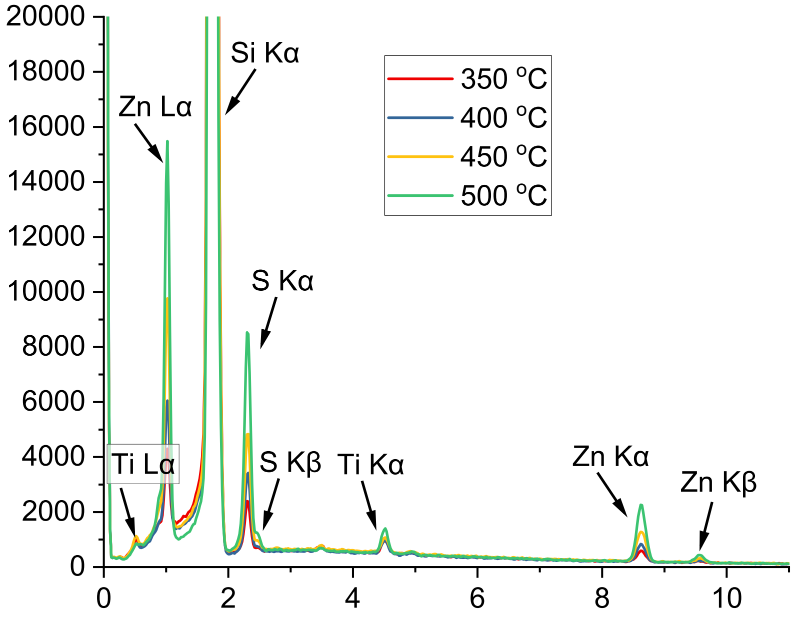

Figure S1: EDX spectra for the ZnS films that were deposited on Ti at 350, 400, 450, and 500 °C.

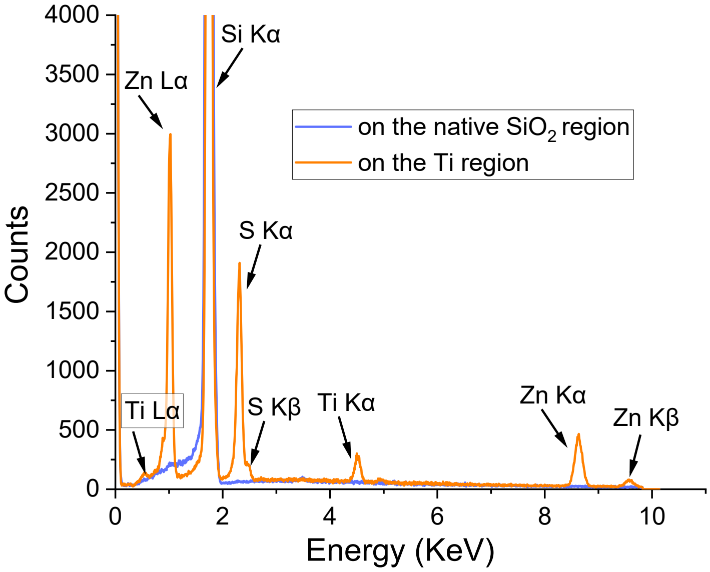

Figure S2: EDX spectra measured on the Ti and native SiO_2 regions on the Ti/native SiO_2 patterns after the ZnS deposition.